March 7 – 10, 2023 / COEX Seoul, Korea

### 12E. Manufacturing Process Control

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<th>Session Date:</th>
<th>March 8 (Wed.), 2023</th>
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<td>Session Time:</td>
<td>13:30-15:00</td>
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<td>Session Room:</td>
<td>Room E (#308 a)</td>
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<td>Session Chair:</td>
<td>Prof. Min Hyuk Park (Seoul National University)</td>
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<td>Prof. Woongkyu Lee (Soongsil University)</td>
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#### [12E-1] [Invited] 13:30-13:55

**Process Control Challenges and Solutions for Advanced Semiconductor Devices**

Yun Jung Jee¹, Sang Hyun Han² and Shay Wolfling³

¹Nova Measuring Instruments LTD, ²Nova Measuring Instruments, Inc. ³Nova LTD.

#### [12E-2] [Invited] 13:55-14:20

**Hybrid SPM Metrology and Defect Inspection Technologies in Advanced Process Control**

ByungWoon Ahn, Ahjin Jo and Sang-Joon Cho

*Park Systems Corp.*

#### [12E-3] 14:20-14:40

**In-line SIMS Enables Better SiGe Epi Process Control for Nanosheets**

Lawrence Rooney, Benjamin Hickey, Bruno Schueler, Sarah Okada and Feng Zhang

*Nova Inc.*

#### [12E-4] 14:40-15:00

**Budgeting and Predicting Pattern Defects Using Edge Placement Error and Machine Learning**

Taekwon Jee¹, Joongsang You¹, Hong-Goo Lee¹, Sang-Ho Lee¹, Seungmo Hong¹, Jaewook Seo¹, Roi Meir², Noam Oved², Jun Park², Shin-Ik Kim², Byung-Jo Lim², Chan-Hee Kwak² and Jeong-Ho Yeo²

¹SK hynix, ²Applied Materials